



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Sarah J. Lane et al.

Application No.: 10/788,654

Filed: 2/27/2004

Title: COMPOSITIONS AND METHODS
FOR CHEMICAL MECHANICAL
POLISHING SILICA AND SILICON
NITRIDE

Art Unit:

1755

Examiner:

Unknown

Attorney Docket No.: 03052US

REQUEST FOR CORRECTION

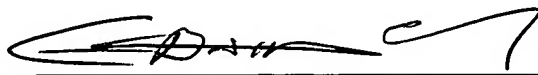
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Sir:

Petitioner hereby requests a correction in the Filing Receipt of the above-referenced patent application. Enclosed is a copy of the Filing Receipt with the changes noted thereon.

Respectfully submitted,

6/16/04
Date


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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY. DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/788,654	02/27/2004	1755	770	03052US		10	3

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CONFIRMATION NO. 7256

FILING RECEIPT



OC000000012736799

Date Mailed: 05/21/2004

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please write to the Office of Initial Patent Examination's Filing Receipt Corrections, facsimile number 703-746-9195. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

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CHARLES YU, WILMINGTON, DE

Domestic Priority data as claimed by applicant

Foreign Applications

If Required, Foreign Filing License Granted: 05/20/2004

Projected Publication Date: To Be Determined - pending completion of Missing Parts

Non-Publication Request: No

Early Publication Request: No

Title

Compositions and methods for chemical mechanical polishing silica and silicon nitride

Preliminary Class

051

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Title 37, Code of Federal Regulations, 5.11 & 5.15**

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